ABSTRACT

Disclosed are a substrate holding device and a wet processing apparatus. The substrate holding device comprises a rotary chuck (200), wherein the rotary chuck (200) includes an intermediate channel (220) , the rotary chuck (200) is used to rotate about the axis of the intermediate channel (220); a guide groove (230) extending radially from inside to outside is provided on the top of the rotary chuck (200), the guide groove (230) has a first side wall (231), a plurality of second side walls (232), and a bottom wall (233), the first side wall (231) is disposed around the periphery of the intermediate channel (220), the plurality of second side walls (232) are spaced apart along the circumferential direction at the edge of the rotary chuck (200), the bottom wall (233) is connected to the first side wall (231) and the plurality of second side walls (232), and the first side wall (231), the plurality of second side walls (232), and the bottom wall (233) are used to make the guide groove (230) include an annular flow channel and a plurality of radial flow channels in communication with each other, wherein the annular flow channel surrounds the intermediate channel (220), and the plurality of radial flow channels extend from the annular flow channel to the edge of the rotary chuck (200). The substrate holding device can prevent accumulated liquid on the rotary chuck (200) from seeping into the interior of the intermediate channel (220) of the rotary chuck (200), thereby preventing the seeped liquid from corroding components inside the intermediate channel (220).